

Release date: 16 February 2010

## Oxford Instruments offers improved end-pointing with its CCD1 Spectrometer System Upgrade



OIPT System100  
ICP Tool

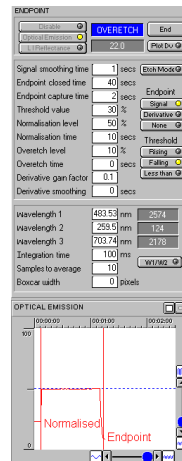


Fig. 1. Endpointing using  
the CCD1

Oxford Instruments Plasma Technology (OIPT) is pleased to announce improved end-pointing capability on its range of plasma etch and deposition tools, with the introduction of the CCD1 Spectrometer system. The CCD1 is capable of providing both a process endpointing capability, and UV/VIS spectrum capture, and is available as a standard option on all new tools or as an upgrade option for existing Oxford Instruments customers.

This spectrometer provides a cost-effective route to general purpose endpointing and spectroscopy, without compromising on resolution or signal strength.

The CCD1 is a UV/VIS CCD spectrometer that can monitor a wide range of plasma emissions over wavelengths 200nm-880nm. This unit can be used in one of two ways: process endpoint detection via OIPT's **PC2000™** software, or full spectrum viewing and recording. This provides the user with detailed plasma spectroscopy information, which can be used for monitoring the concentrations of species within the plasma. The spectra can also be compared to previous spectral data – for system monitoring, fault detection and potential fault classification.

Now available as a system option on new OIPT etch and deposition tools, the CCD1 spectrometer may also be offered as an upgrade to systems in the field, dependent on the system age, type, and configuration.

-ends-



Issued for and on behalf of Oxford Instruments Plasma Technology Limited

**For further information and electronic copies of the images please contact:**

**Susie Williams**

**Marketing Communications Manager**

**Oxford Instruments Plasma Technology**

**e. [susie.williams@oxinst.co.uk](mailto:susie.williams@oxinst.co.uk)**

**t. +44 (0)1934 837000**

**f. +44 (0)1934 837001**

#### **About Oxford Instruments plc**

Oxford Instruments aims to pursue responsible development and deeper understanding of our world through science and technology. We provide high technology tools and systems for industrial and research markets, based on our ability to analyse and manipulate matter at the smallest scale. Innovation has been the driving force behind Oxford Instruments' growth and success for over 50 years, and its strategy is to effect the successful commercialisation of these ideas by bringing them to market in a timely and customer-focused fashion.

The first technology business to be spun out from Oxford University over fifty years ago, Oxford Instruments is now a global company with over 1,300 staff worldwide and a listing on the London Stock Exchange (OXIG).

Our objective is to be a leading supplier of next generation tools and systems for research and industry. This involves the combination of core technologies in areas such as low temperature and high magnetic field environments, Nuclear Magnetic Resonance, X-ray electron and optical based metrology, and advanced growth, deposition and etching. Our products, expertise, and ideas address global issues such as energy, environment, terrorism and health and are part of the next generation of telecommunications, energy products, environmental measures, security devices, drug discovery and medical advances.

#### **About Oxford Instruments Plasma Technology**

Oxford Instruments Plasma Technology offers flexible, configurable process tools and leading-edge processes for the precise, controllable and repeatable engineering of micro- and nano-structures. Our systems provide process solutions for nanometre layer epitaxial growth of compound semiconductor material, etching of nanometre sized features and the controlled growth of nanostructures. These solutions are based on core technologies in plasma-enhanced deposition and etch, ion-beam deposition and etch, atomic layer deposition and hydride vapour phase epitaxy. Products range from compact stand-alone systems for R&D, through batch tools and up to clustered cassette-to-cassette platforms for high-throughput production processing.